

Fig. 1A
SIDE VIEW

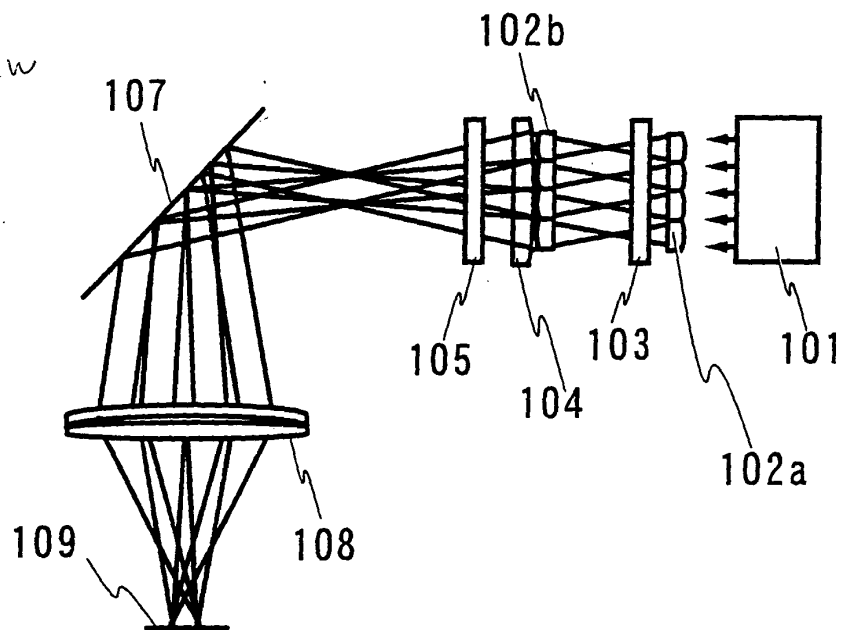
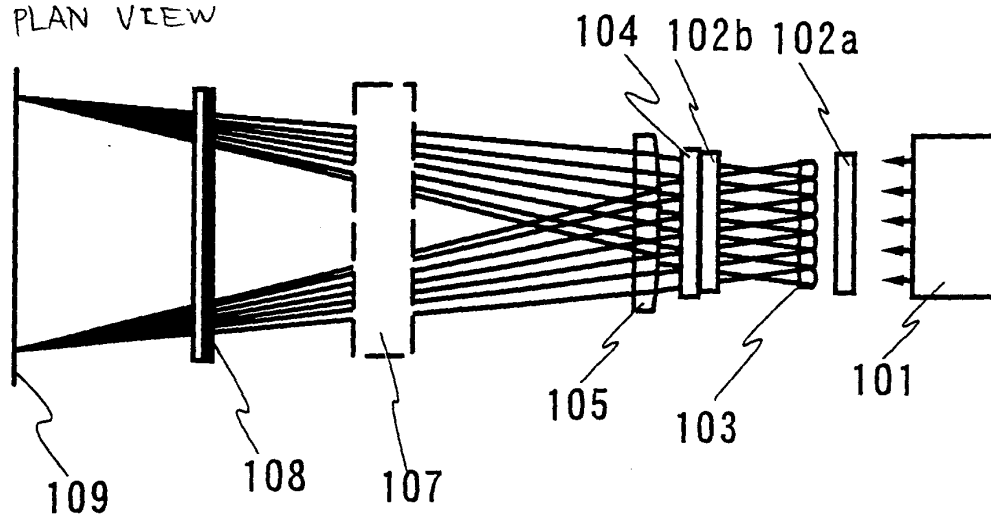


Fig. 1B
PLAN VIEW



65

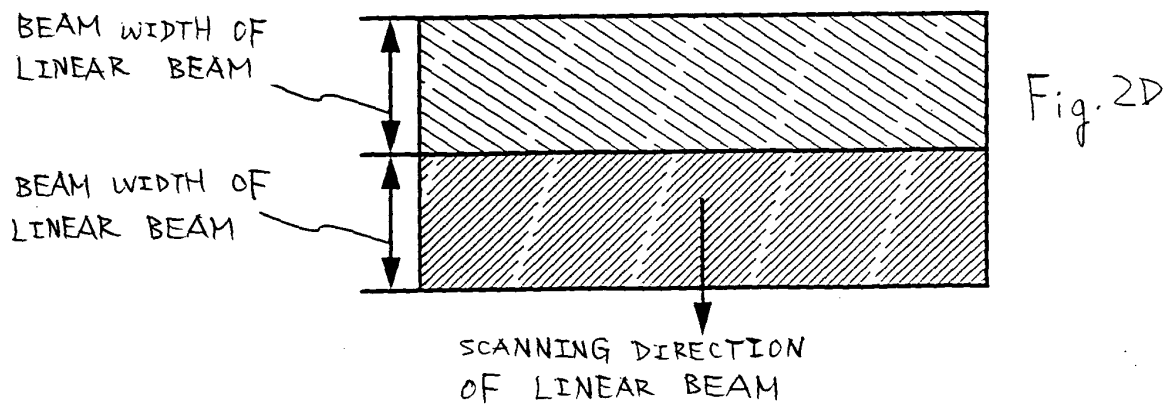
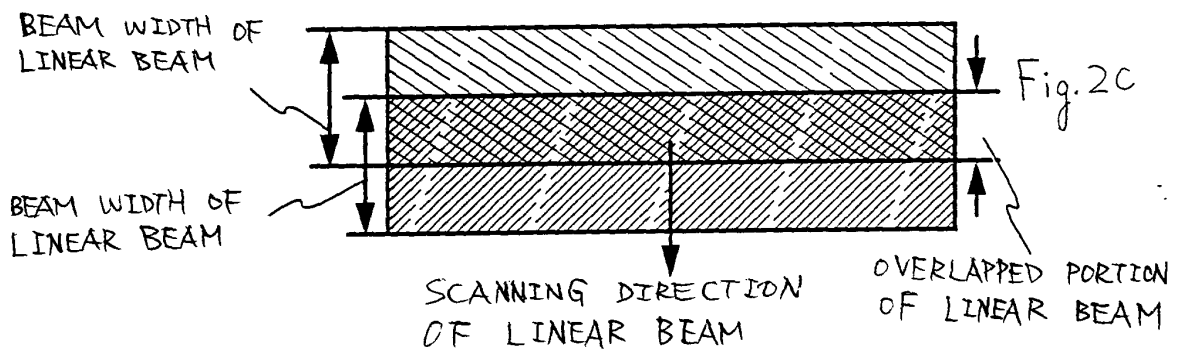
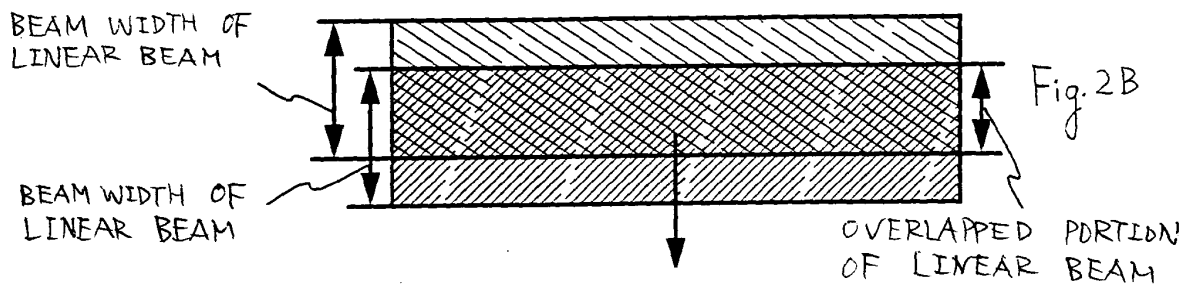
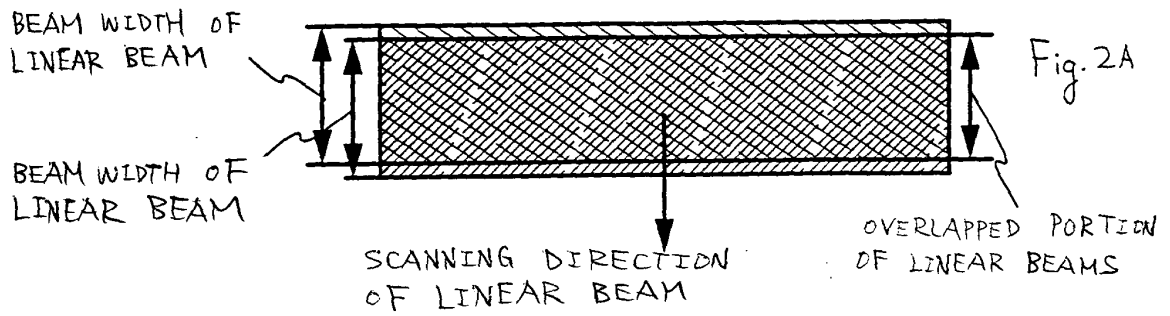


Fig. 3

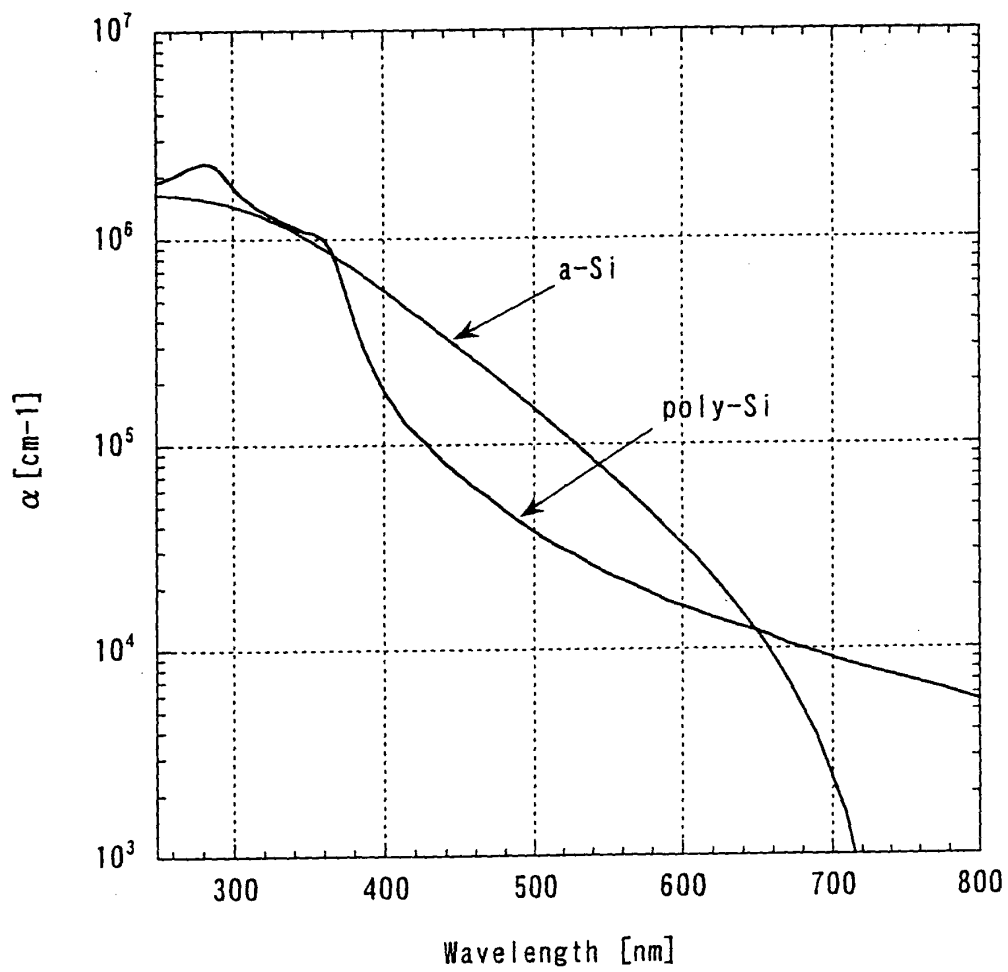


Fig. 4A

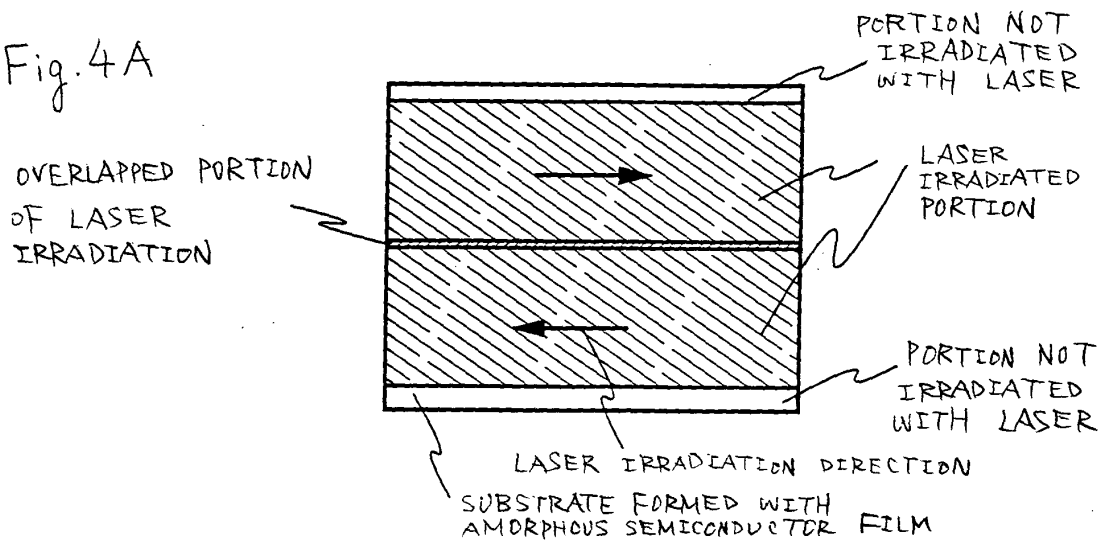


Fig. 4B

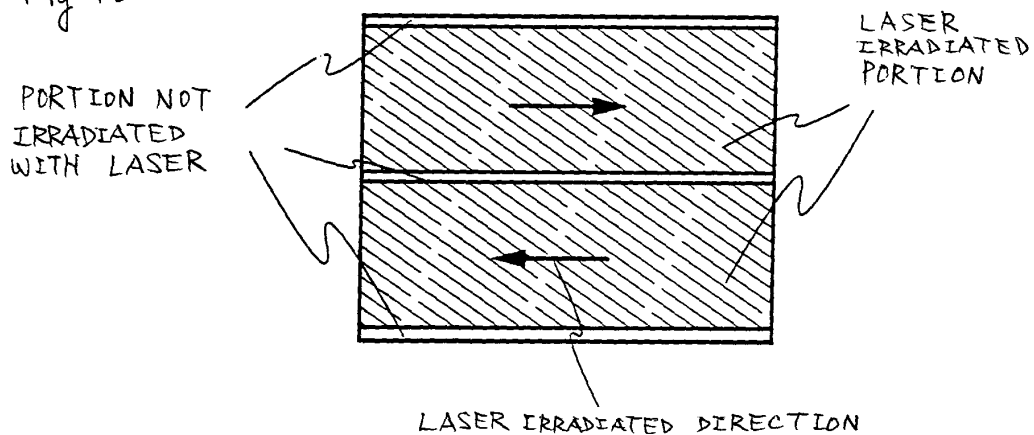


Fig. 4C

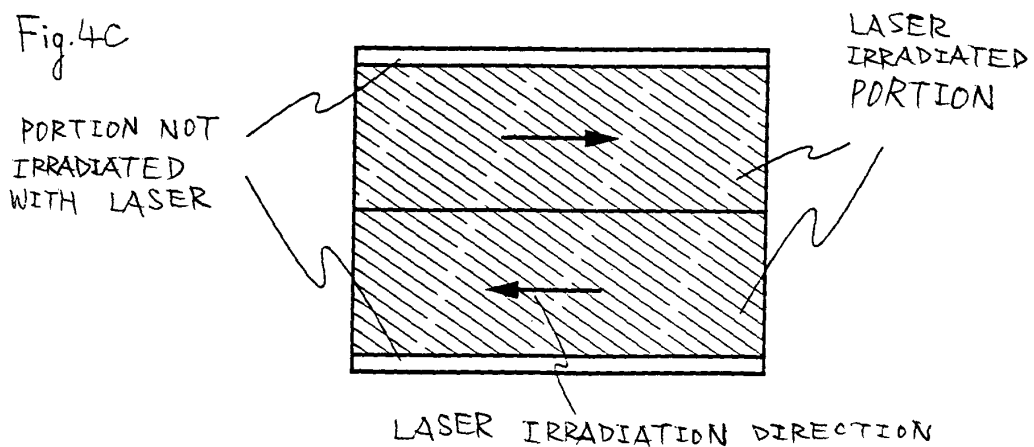


Fig. 5A
SIDE VIEW

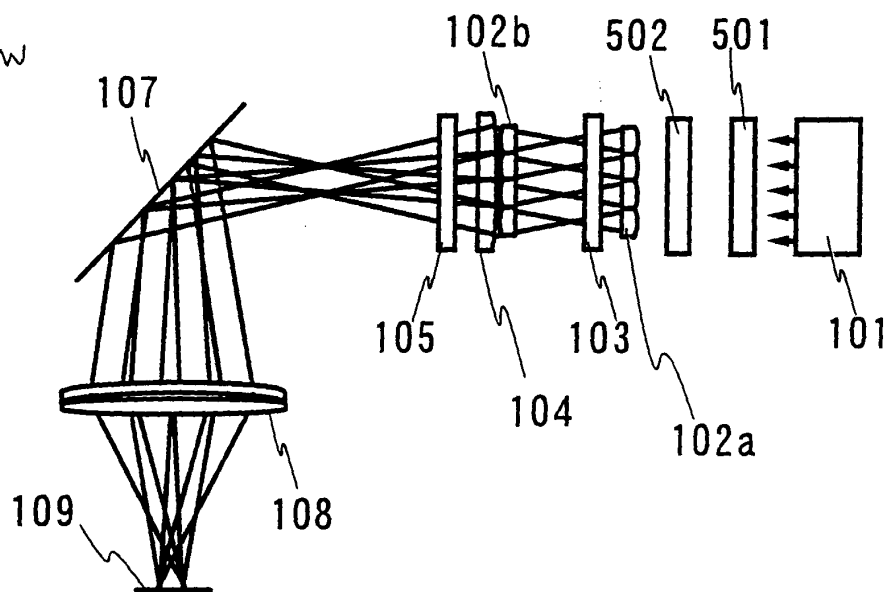
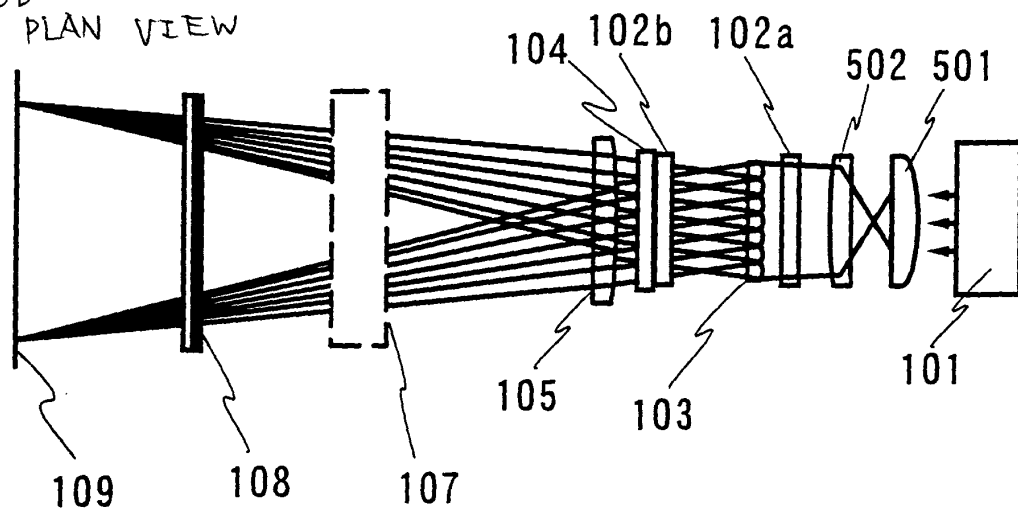
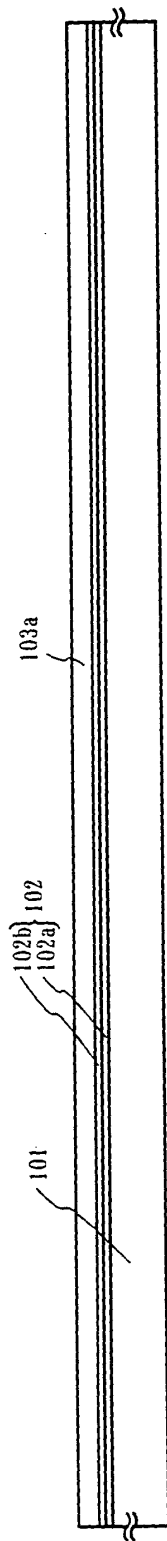


Fig. 5B
PLAN VIEW



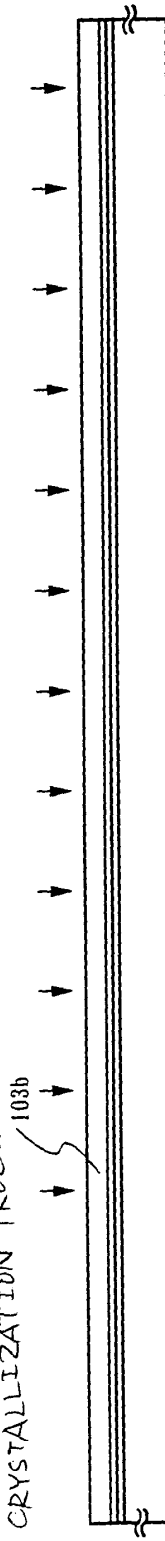
FORMATION OF UNDERLYING FILM AND AMORPHOUS SEMICONDUCTOR FILM

Fig. 6A



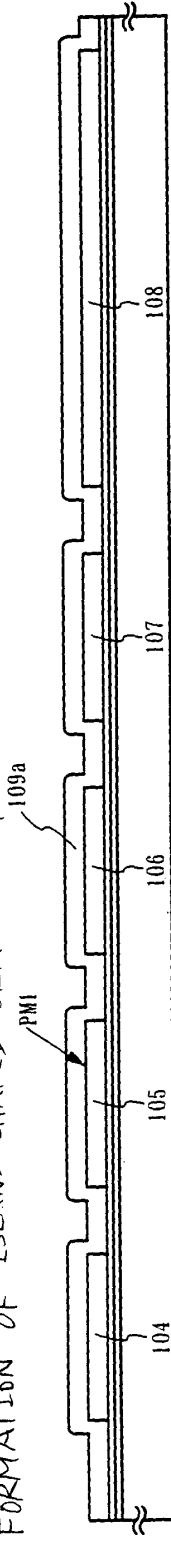
CRYSTALLIZATION PROCESS

Fig. 6B



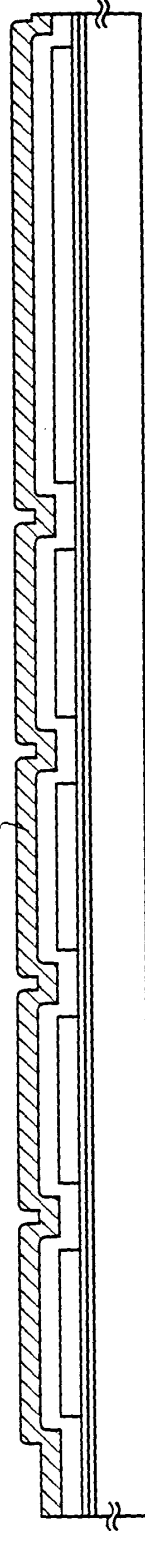
FORMATION OF ISLAND-SHAPED SEMICONDUCTOR LAYER AND GATE INSULATING FILM

Fig. 6C



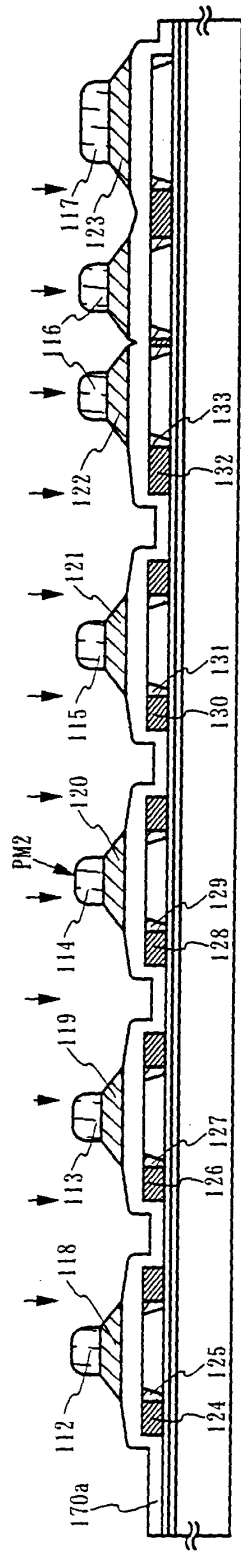
FORMATION OF HEAT-RESISTANT CONDUCTIVE LAYER

Fig. 6D



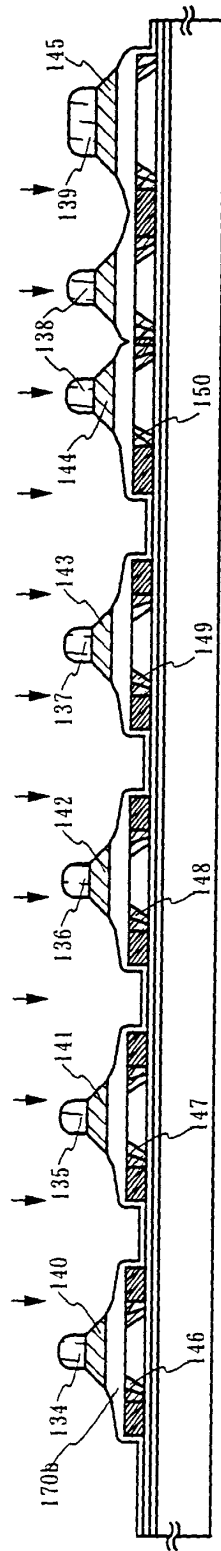
FIRST ETCHING PROCESS / FIRST DOPING PROCESS (n^+)

Fig. 7A



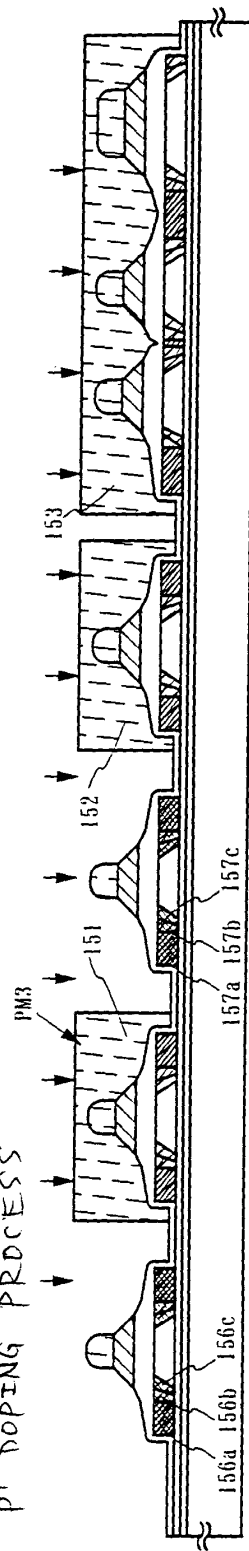
SECOND ETCHING PROCESS / SECOND DOPING PROCESS (n^-)

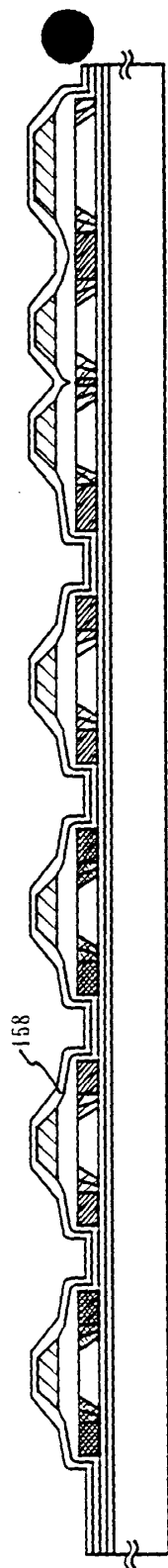
Fig. 7B



p^+ DOPING PROCESS

Fig. 7C





FORMATION OF SECOND INTERLAYER INSULATING FILM AND CONTACT HOLE

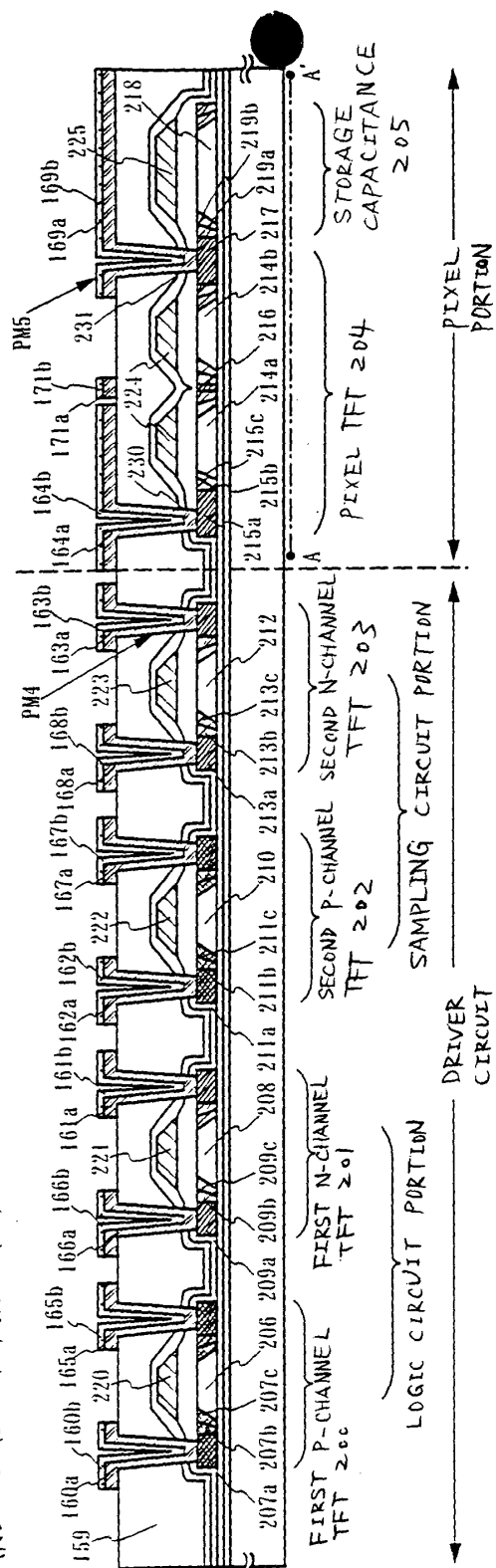
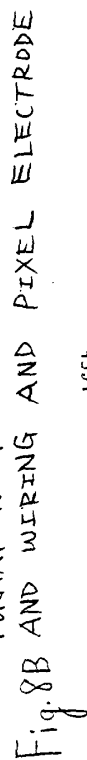


Fig. 9A

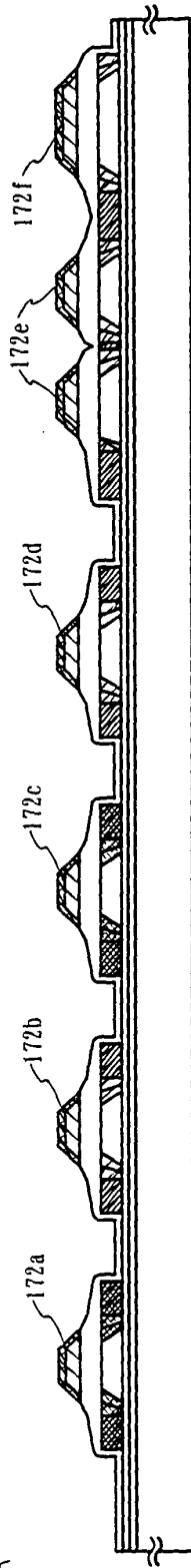


Fig. 9B

FORMATION OF FIRST INTERLAYER INSULATING FILM

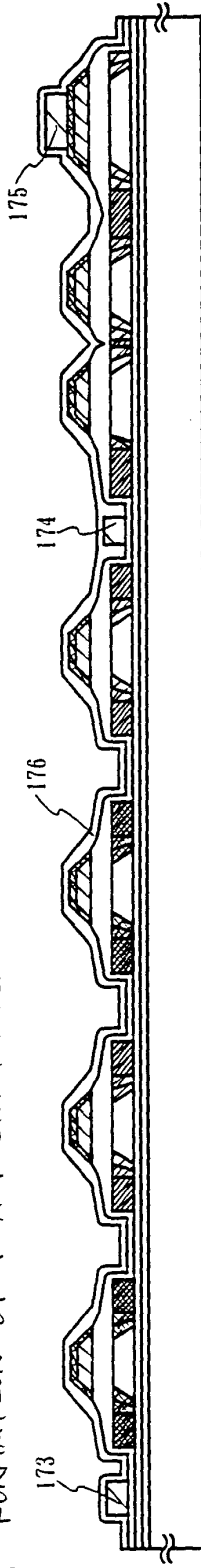
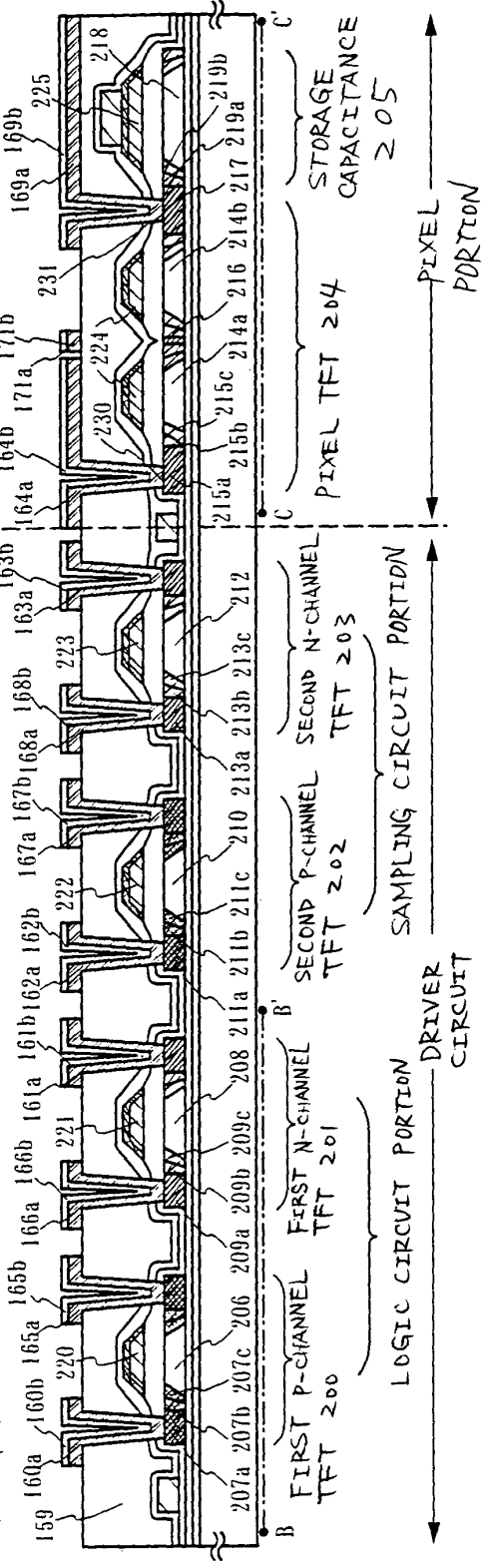


Fig. 9C

FORMATION OF SECOND INTERLAYER INSULATING FILM AND CONTACT HOLE AND WIRING



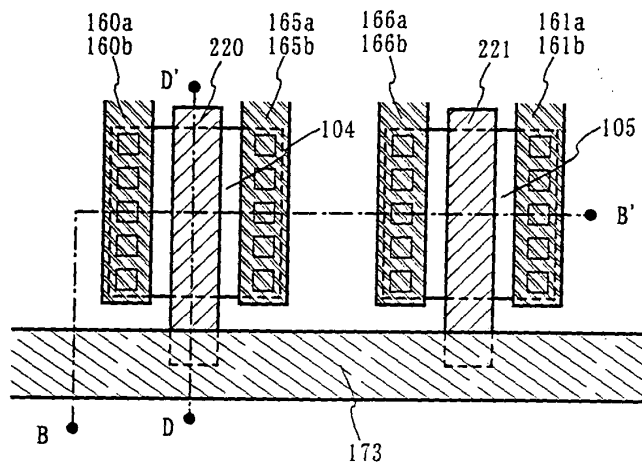


Fig. 10A

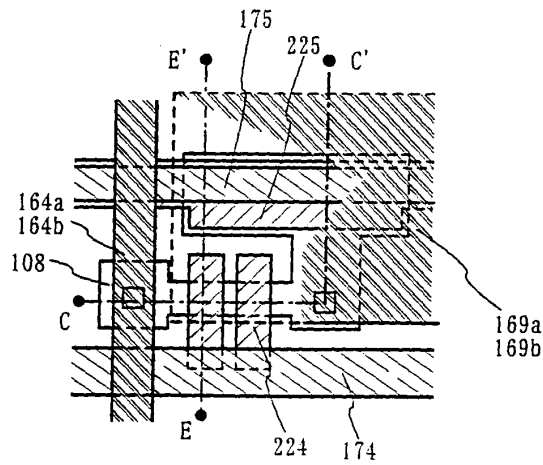


Fig. 10B

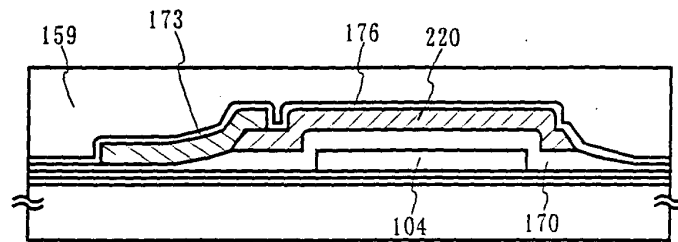


Fig. 11A

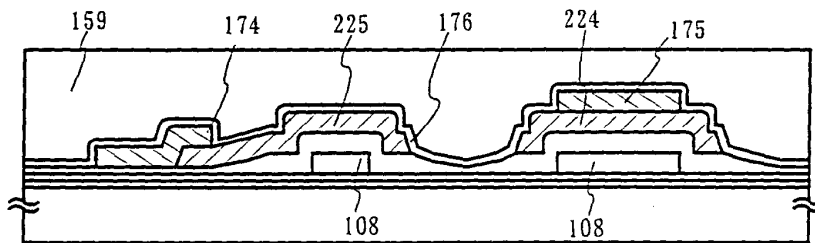
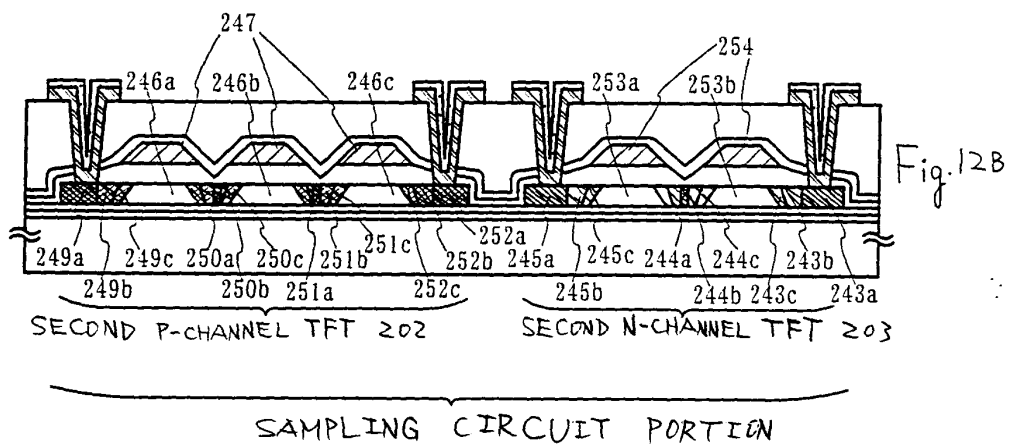
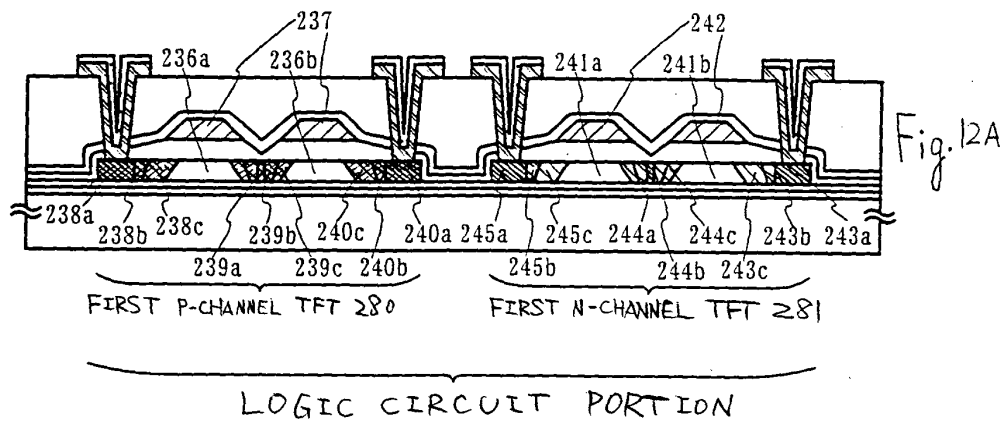
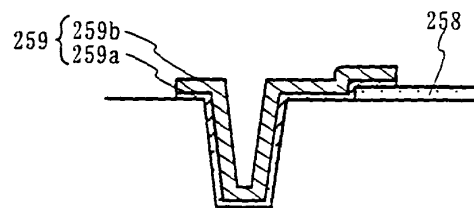
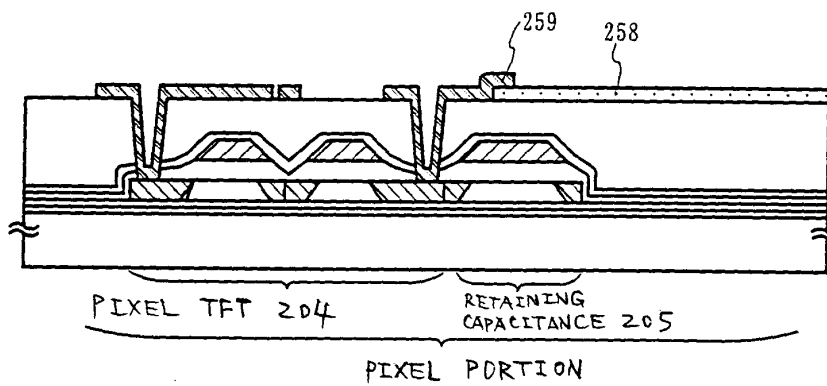
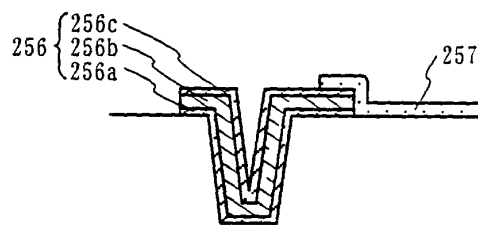
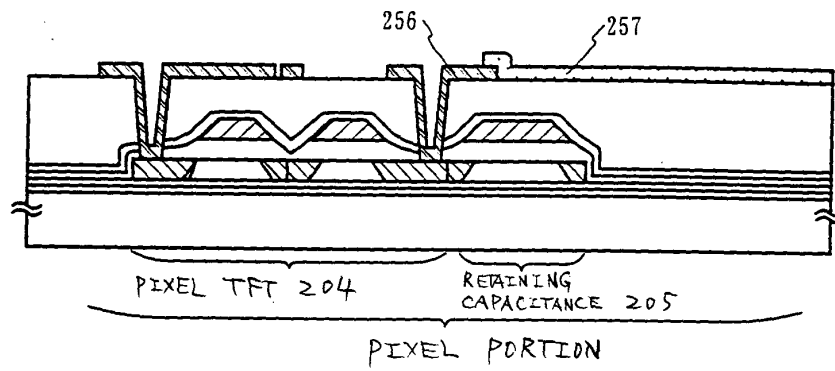


Fig. 11B





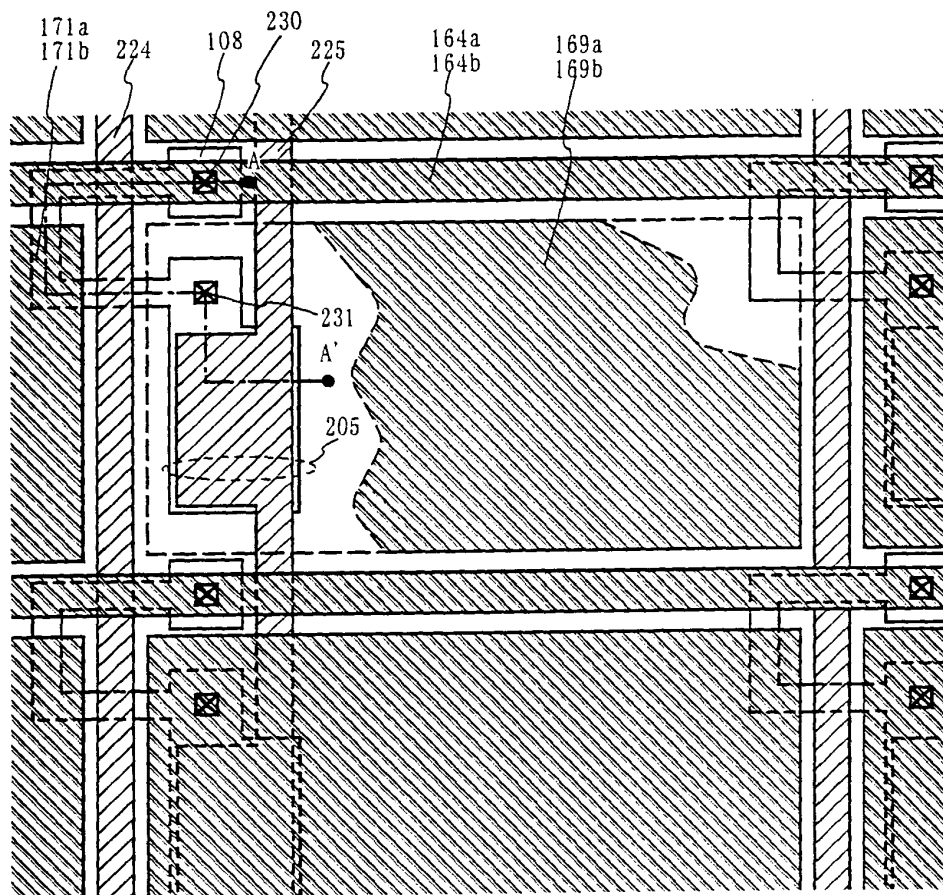


Fig. 14

FIG. 15A is a cross-sectional view of a pixel portion of a display device, showing a first p-channel TFT 200, a first n-channel TFT 201, a second p-channel TFT 202, a second n-channel TFT 203, a pixel TFT 204, and a storage capacitor 205. The pixel portion is defined by a pixel circuit portion and a driver circuit. The pixel circuit portion includes the first p-channel TFT 200, the first n-channel TFT 201, the second p-channel TFT 202, and the second n-channel TFT 203. The driver circuit includes the pixel TFT 204 and the storage capacitor 205. The pixel portion is further defined by a pixel circuit portion and a driver circuit. The pixel circuit portion includes the first p-channel TFT 200, the first n-channel TFT 201, the second p-channel TFT 202, and the second n-channel TFT 203. The driver circuit includes the pixel TFT 204 and the storage capacitor 205.

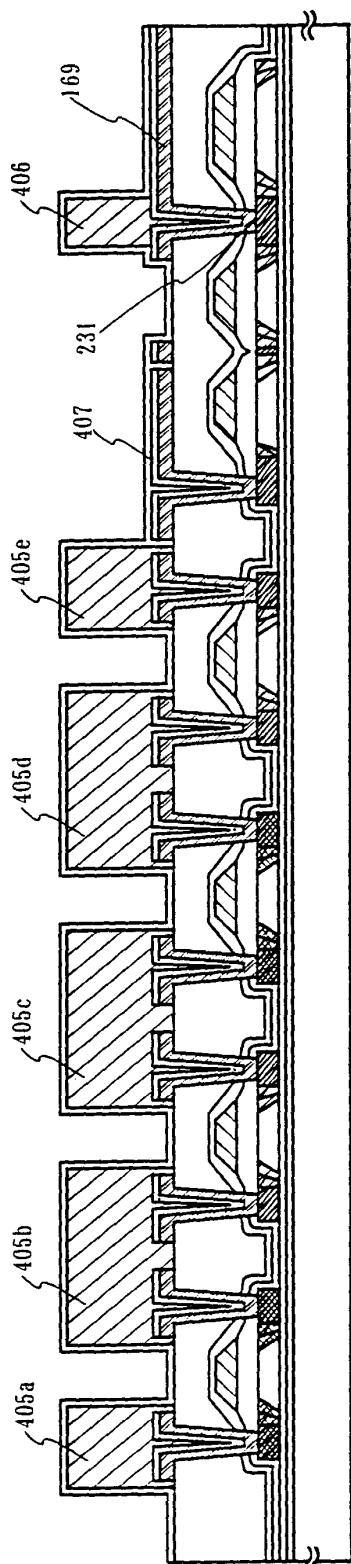


Fig. 15A

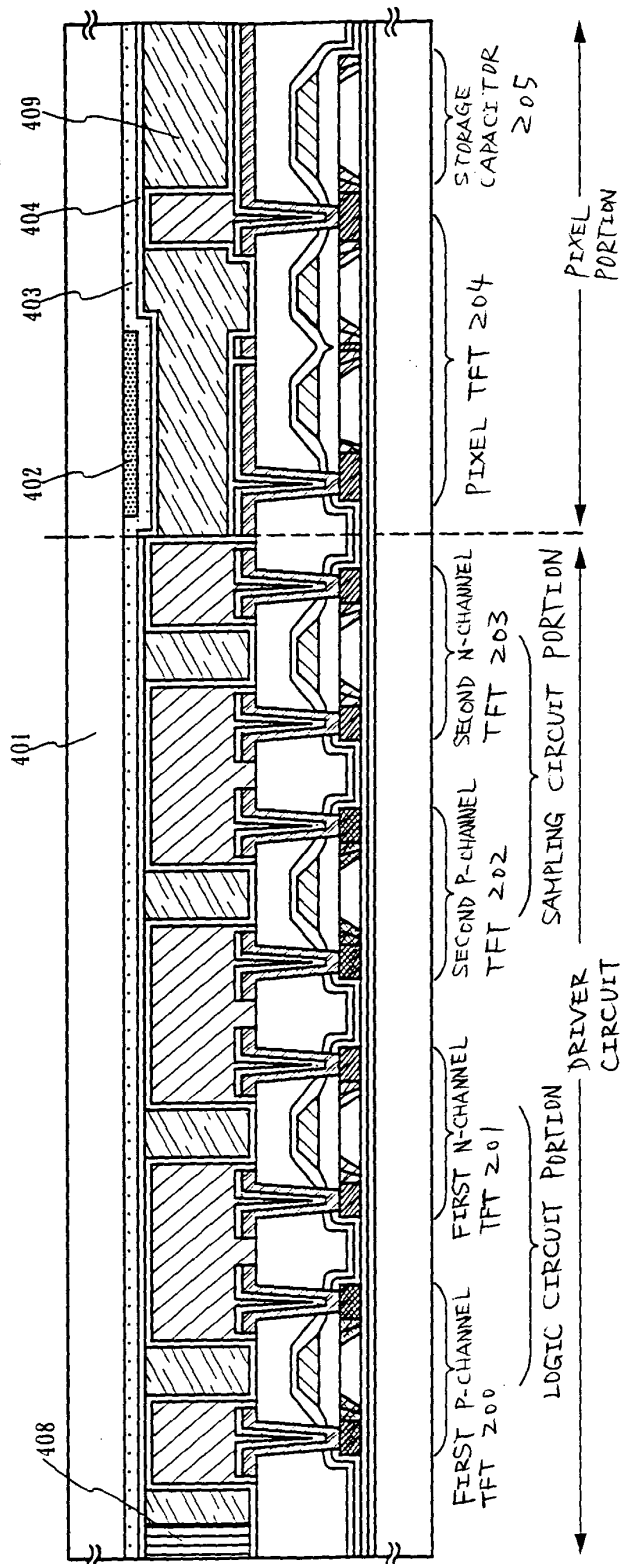


Fig. 15B

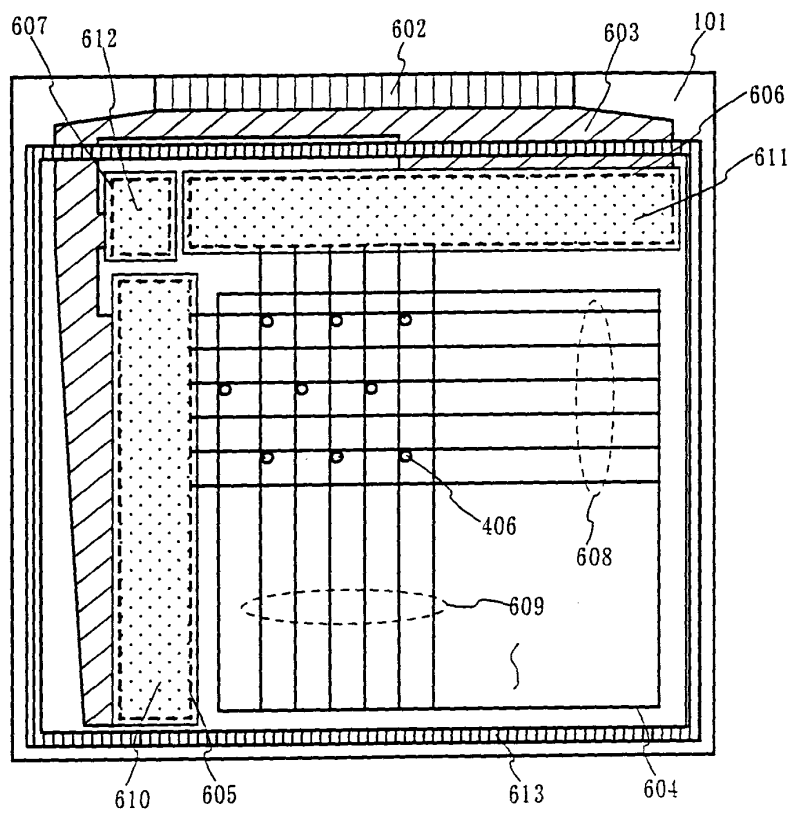


Fig. 16

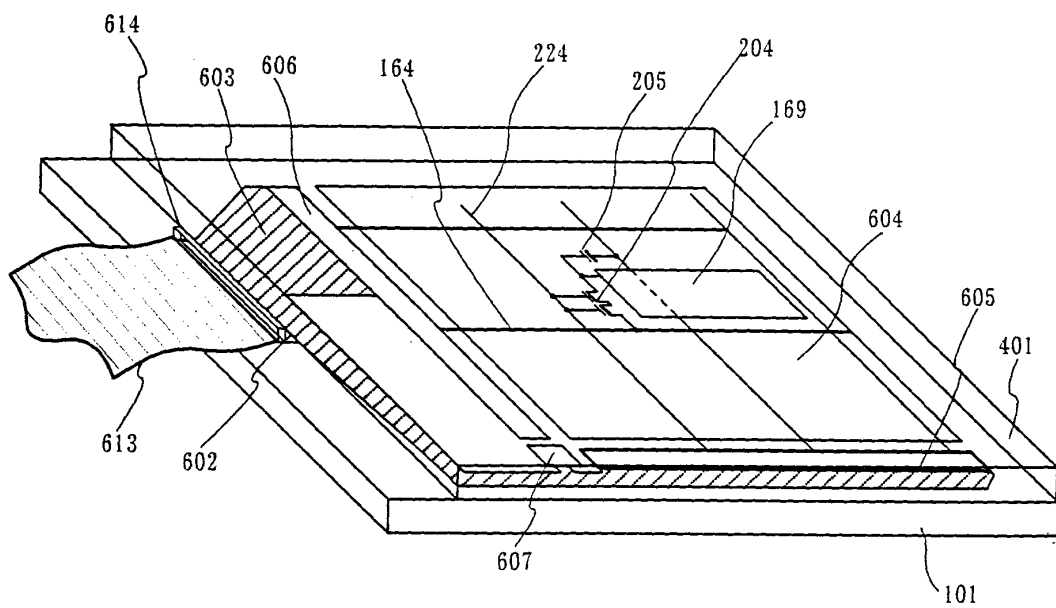


Fig. 17

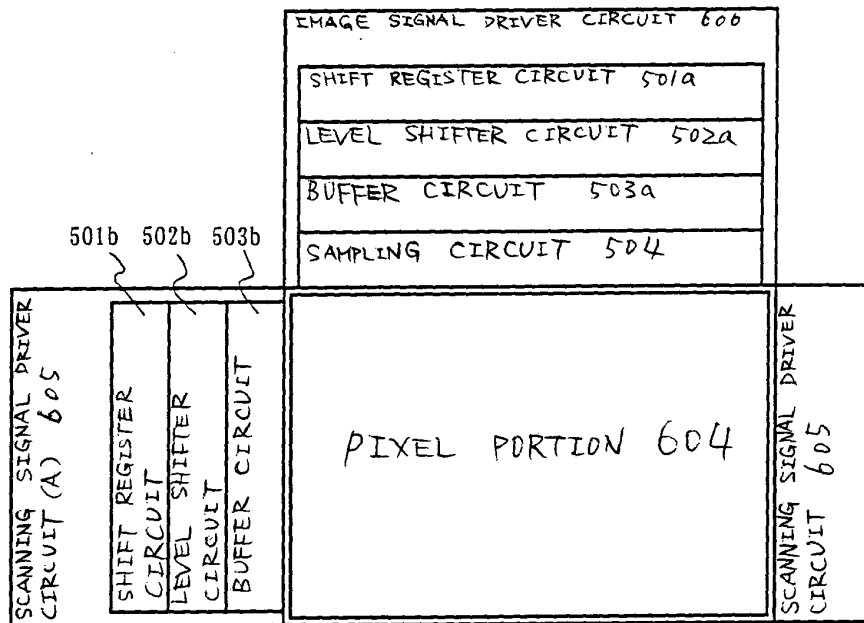
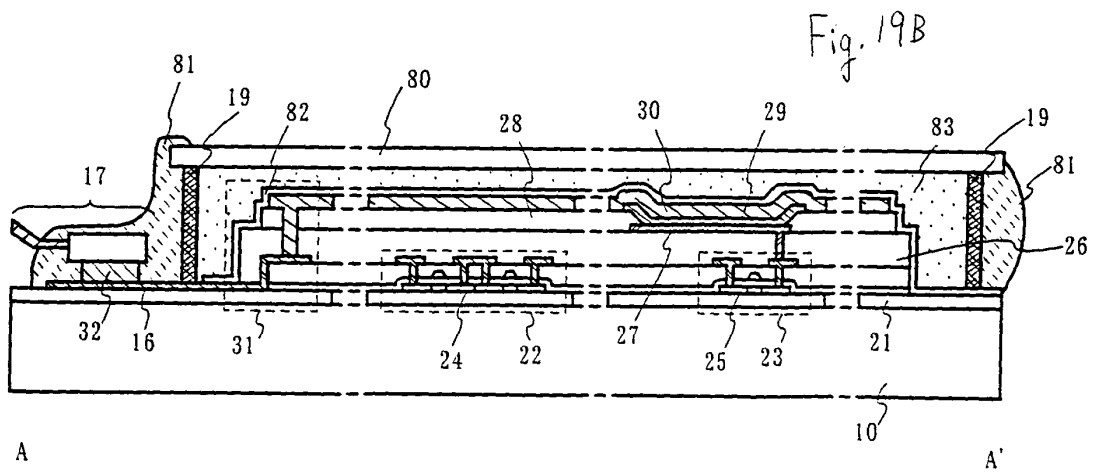
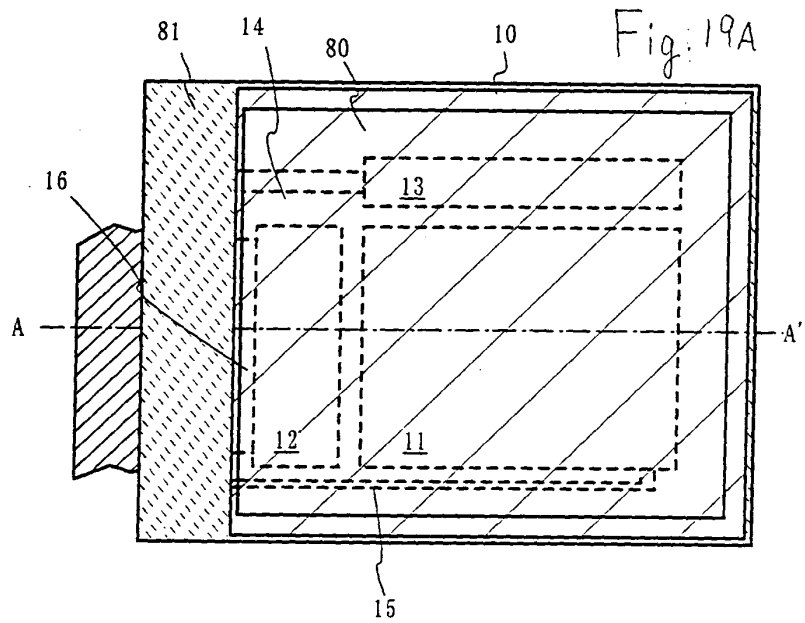


Fig. 18



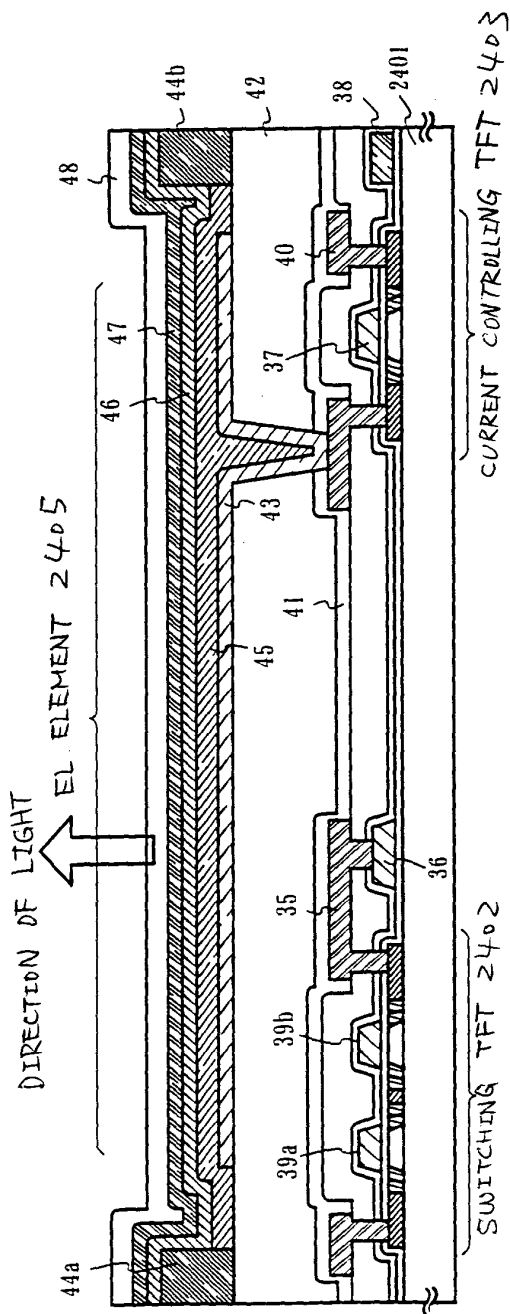


Fig. 20A

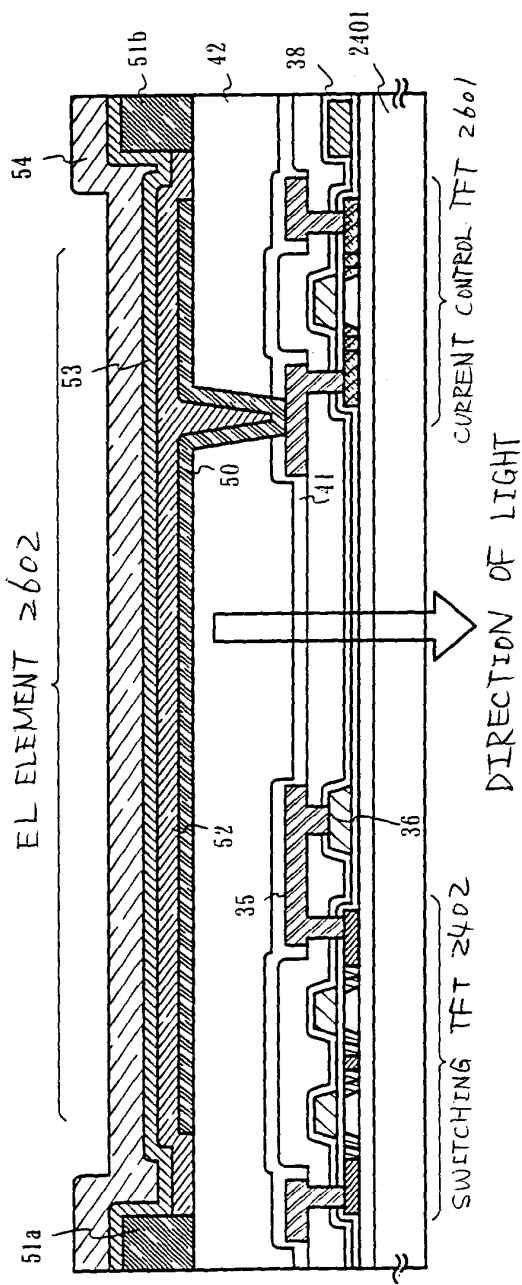


Fig. 20B

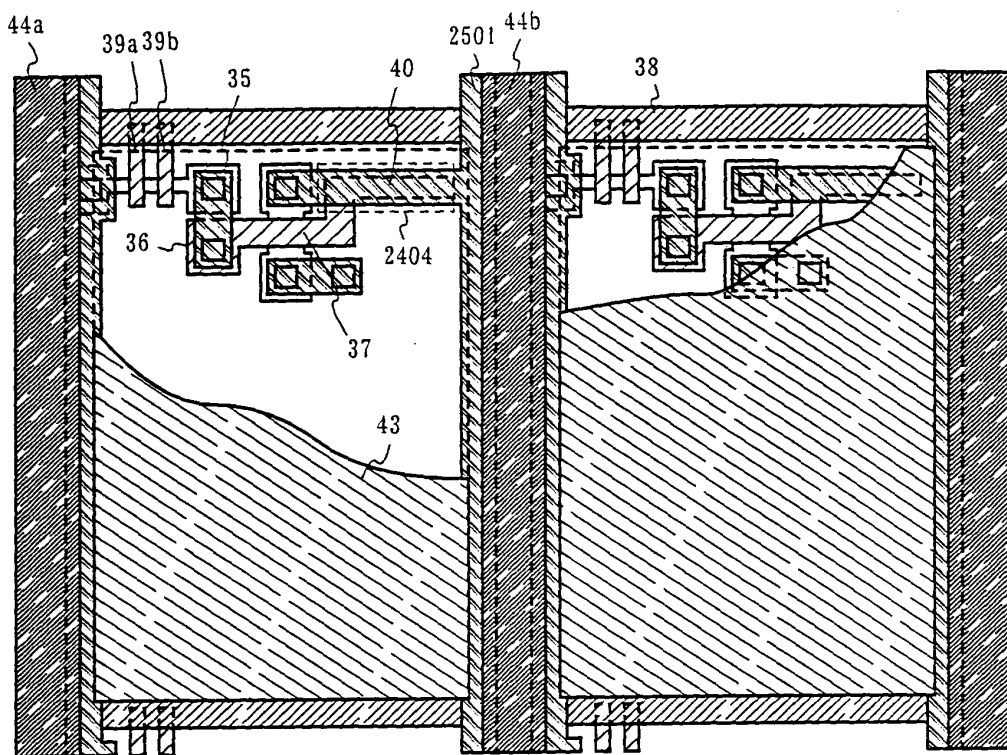


Fig. 21A

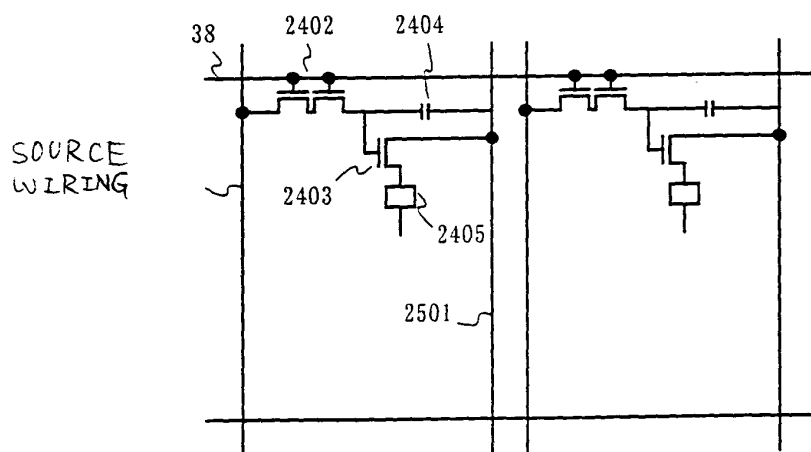


Fig. 21B

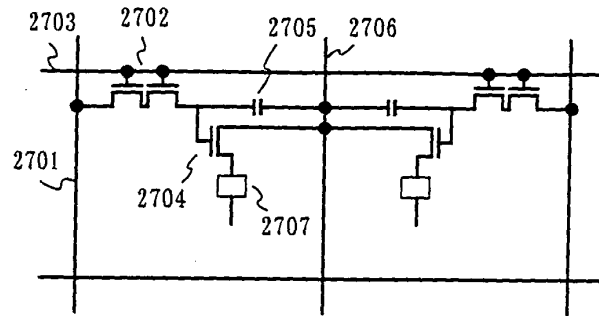


Fig. 22A

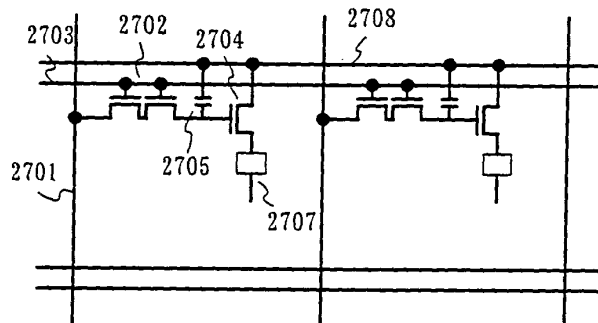


Fig. 22B

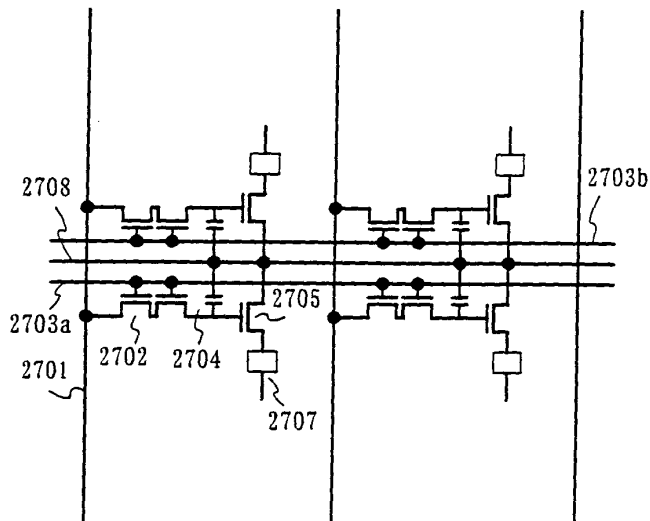


Fig. 22C

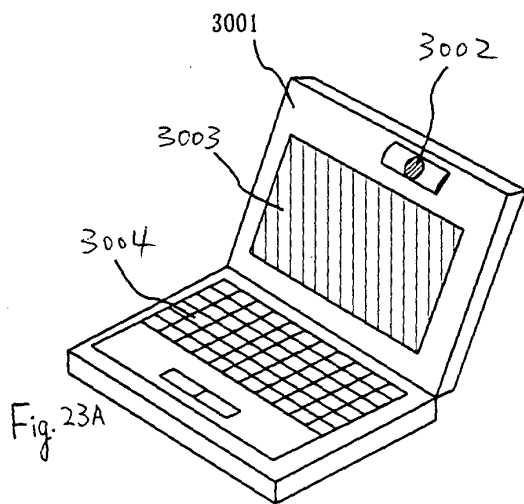


Fig. 23A

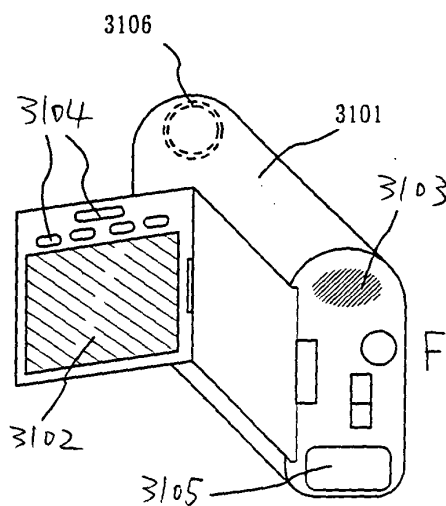


Fig. 23B

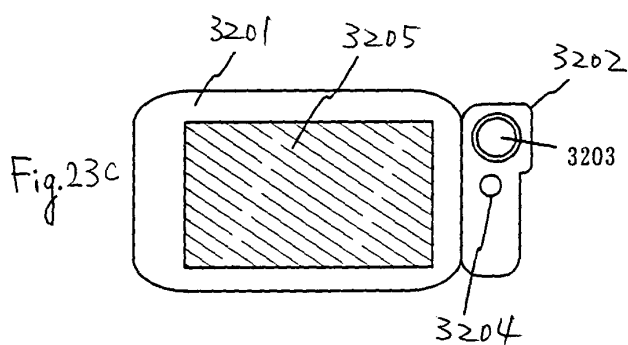


Fig. 23C

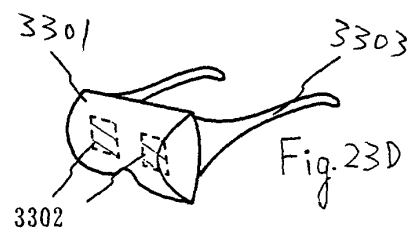


Fig. 23D

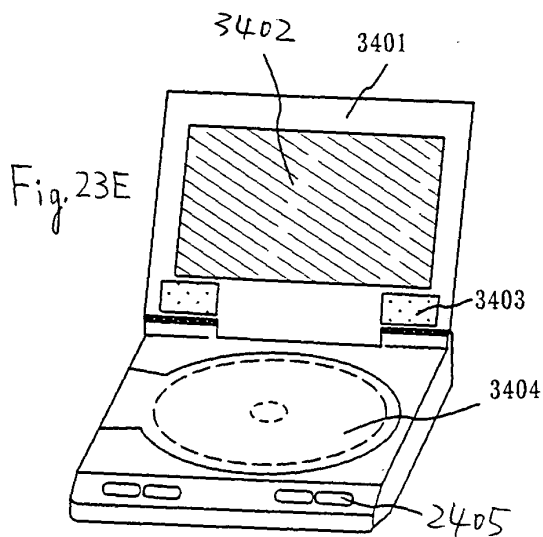


Fig. 23E

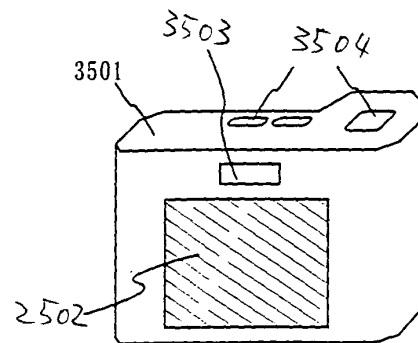


Fig. 23F

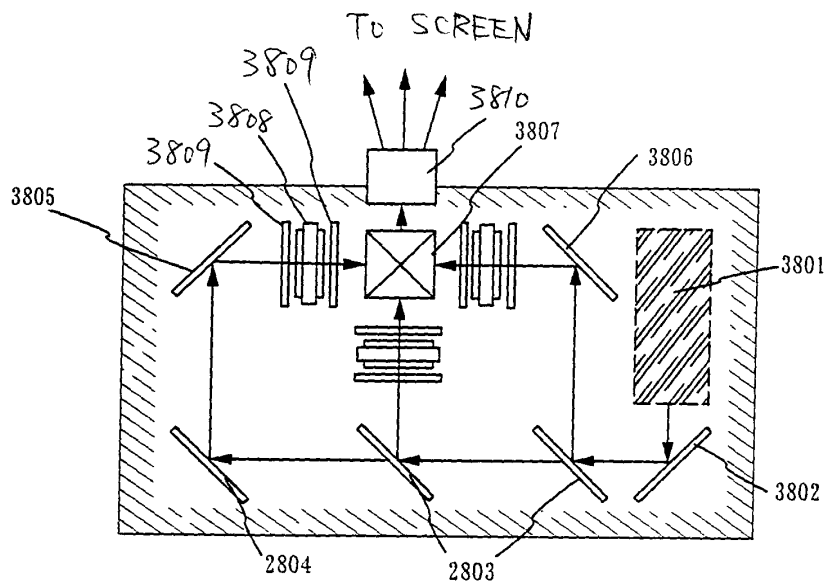
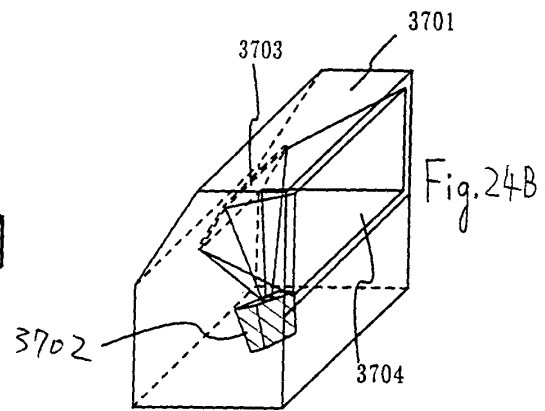
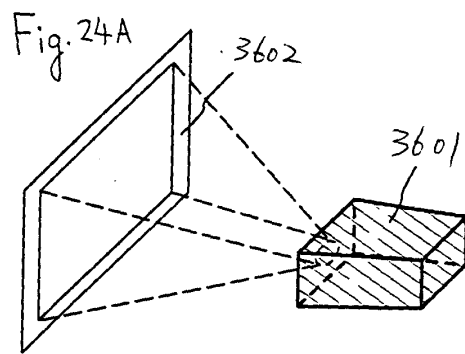


Fig. 24C PROJECTION DEVICE (THREE PLATE TYPE)

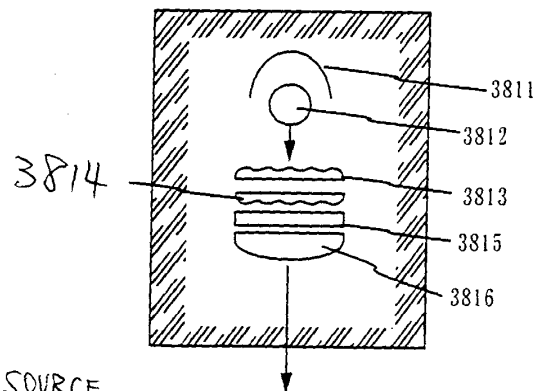


Fig. 24D LIGHT SOURCE OPTICAL SYSTEM

